

<b>Session Title:</b>	<b>[TC1] Plasma Etch Measurements &amp; Diagnostics</b>
<b>Session Date:</b>	<b>November 15 (Tue.), 2022</b>
<b>Session Time:</b>	<b>09:30-10:40</b>
<b>Session Room:</b>	<b>Room C (Grand Ballroom 2, 2F)</b>
<b>Session Chair:</b>	<b>Prof. Jin Wook Jeong (Hanyang Univ., Korea)</b>

**[TC1-1] [Invited] 09:30-10:00**

**Why you should use Hairpin-Probe and Not Langmuir-Probe for Negative-Ion Density via Laser Photo-Detachment**

**Albert R. Ellingboe, Nishant Sirse (Dublin City Univ., Ireland), and Nourredine Oudine (Plasmionique, Canada)**

**[TC1-2] 10:00-10:20**

**Development of In-situ Non-Invasive Sensor for Plasma Uniformity Monitoring**

**Sijun Kim, Minsu Choi (Chungnam Nat'l Univ., Korea), Sangho Lee (KIMM, Korea), Youngseok Lee, Chulhee Cho, Inho Seong, Wonnyoung Jeong, Yebin You (Chungnam Nat'l Univ., Korea), Jangjae Lee (Samsung Electronics Co., Ltd., Korea), Daewoong Kim (KIMM, Korea)**

**[TC1-3] 10:20-10:40**

**Plasma Potential Measurement Method of the Floated Emissive Probe**

**Chulhee Cho, Sijun Kim, Youngseok Lee, Inho Seong, Wonnyoung Jeong, Yebin You, Minsu Choi, and Shinjae You (Chungnam Nat'l Univ., Korea)**